Notice of Allowability	Application No.	Applicant(s)
	10/711,394	ANDERSON ET AL.
	Examiner	Art Unit
	Hsien-ming Lee	2823
The MAILING DATE of this communication app All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85 NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT R of the Office or upon petition by the applicant. See 37 CFR 1.313	ears on the cover sheet with the (OR REMAINS) CLOSED in this ) or other appropriate communicated HGHTS. This application is subjection	application. If not included tion will be mailed in due course. THIS
1. This communication is responsive to 4/11/2007.		
2. ☑ The allowed claim(s) is/are <u>1-14</u> .		
<ol> <li>Acknowledgment is made of a claim for foreign priority up a)</li></ol>	e been received. e been received in Application No. comments have been received in the discrepance of this communication to file a reposition. The second of this application.	nis national stage application from the oly complying with the requirements
5. CORRECTED DRAWINGS ( as "replacement sheets") must (a) including changes required by the Notice of Draftspers 1) hereto or 2) to Paper No./Mail Date  (b) including changes required by the attached Examiner Paper No./Mail Date  Identifying indicia such as the application number (see 37 CFR 1 each sheet. Replacement sheet(s) should be labeled as such in 16. DEPOSIT OF and/or INFORMATION about the deposit attached Examiner's comment regarding REQUIREMENT.	st be submitted. son's Patent Drawing Review ( PT 's Amendment / Comment or in the 1.84(c)) should be written on the dra the header according to 37 CFR 1.12 osit of BIOLOGICAL MATERIA	O-948) attached  e Office action of  wings in the front (not the back) of 21(d).  L must be submitted. Note the
<ul> <li>Attachment(s)</li> <li>1. ☑ Notice of References Cited (PTO-892)</li> <li>2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948)</li> <li>3. ☑ Information Disclosure Statements (PTO/SB/08), Paper No./Mail Date 20040916 &amp; 20050118</li> <li>4. ☐ Examiner's Comment Regarding Requirement for Deposit of Biological Material</li> </ul>	Paper No./Mail I 7. 🛛 Examiner's Amer	ary (PTO-413), Date
		Primary Examiner Art Unit: 2823

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## **DETAILED ACTION**

## Examiner's Amendment

1. An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

Authorization for this examiner's amendment was given in a telephone interview with Jack P. Friedman (Reg. No. 44,688) on June 18, 2007.

2. The application has been amended as follows:

In specification, page 7, on line 6, replace "oxy nitride" with -- oxynitride --; and on line 7, replace "oxy carbide" with -- oxycarbide --.

In specification, page 6, [para 25], line 5, replace "115" with -- 120 --.

Cancel claims 15-30.

In claim 1, on line 7, delete "," after "through" and on line 10, replace "a" with – an – before "electrical."

In claim 5, on line 3, insert --, -- after "carbide", on line 3, replace "oxy nitride" with -- oxynitride --; and on line 4, replace "oxy carbide" with -- oxycarbide --.

In claim 6, on line 5, insert -- and -- before "methyl" and delete "and other low dielectric constant materials."

In claim 7, on line 3, insert --, -- after "carbide", on line 3, replace "oxy nitride" with -- oxynitride --; and on line 4, replace "oxy carbide" with -- oxycarbide --.

## Allowable Subject Matter

- 3. Claims 1-14 are allowed.
- 4. The following is an examiner's statement of reasons for allowance:

The closest prior art of record, Schwarzl et al. to US 6,686,643, teaches a related art, comprising: forming a dielectric layer I1 on a substrate; forming a capping layer M on a top surface of said dielectric layer I1; forming a trench through said capping layer M (Fig.1), said trench extending toward said substrate and into but not through said dielectric layer I1; forming a sacrificial layer F on opposing sidewalls of said trench (Fig.2); filling said trench with an insulating layer FS (i.e. SiO<sub>2</sub>); and removing a portion of said sacrificial layer F between said insulating layer FS and a spacer SP to form air-gaps H (Fig.5).

In contrast, Schwarzl et al. neither teach nor suggest filling said trench with an electrical conductor and removing a portion of said sacrificial layer between said electrical conductor and said dielectric layer to form air-gaps. In addition, Schwarzl et al. neither teach nor suggest between steps (f) and (g) forming an extended air gaps under said capping layer by removing at least a portion of said dielectric layer adjacent to said air-gaps; forming a common surface by planarizing said capping layer, said sacrificial layer and said electrical conductor; forming a copolymer layer on said common surface; forming pores in said copolymer layer extending down to said common surface.

In the examiner's opinion, it would not have been obvious to one of the ordinary skill in the art to modify the teachings of Schwarzl et al. to arrive the present invention. In particular, Application/Control Number: 10/711,394 Page 4

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the current invention teaches filling the trench with the electrical conductor, whereas Schwarzl et al. teach filling the trench with the insulator.

5. Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

6. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Hsien-ming Lee whose telephone number is 571-272-1863. The examiner can normally be reached on Tuesday-Thursday  $(7:30 \sim 6:00)$ .

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Matthew Smith can be reached on 571-272-1907. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

Hsien-ming Lee Primary Examiner Art Unit 2823

HSIEN-MING LEE PRIMARY EXAMINER

6/18/07